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| APPLICATION NO. | FILING DATE | FIRST NAMED INVENTOR | ATTORNEY DOCKET NO. | CONFIRMATION NO. |
|--------------------------|-----------------|----------------------|-----------------------|------------------|
| 10/642,656 | 08/19/2003 | Seo-Hyun Cho | 1349.1276 | 3051 |
| 21171 75 | 90 02/01/2006 | | EXAMINER | |
| STAAS & HALSEY LLP | | | MCPHERSON, JOHN A | |
| SUITE 700 1201 NEW YO | RK AVENUE, N.W. | | ART UNIT PAPER NUMBER | |
| WASHINGTON, DC 20005 | | | 1756 | |

DATE MAILED: 02/01/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

| <u> </u> | | | | | |
|--|--|--|---|--------------|--|
| | | Application No. | Applicant(s) | | |
| | | 10/642,656 | CHO ET AL. | CHO ET AL. | |
| | Office Action Summary | Examiner | Art Unit | | |
| | | John A. McPherson | 1756 | | |
| Period fo | The MAILING DATE of this communication Reply | on appears on the cover sh | et with the correspondence a | address | |
| A SH WHIC - Exte after - If NC - Failu Any | IORTENED STATUTORY PERIOD FOR I CHEVER IS LONGER, FROM THE MAILI ensions of time may be available under the provisions of 37 of SIX (6) MONTHS from the mailing date of this communical Diperiod for reply is specified above, the maximum statutory ure to reply within the set or extended period for reply will, by reply received by the Office later than three months after the department of the provided partner of the set of the se | NG DATE OF THIS COMN CFR 1.136(a). In no event, however, toon. period will apply and will expire SIX (if y statute, cause the application to become | MUNICATION. may a reply be timely filed 6) MONTHS from the mailing date of this pme ABANDONED (35 U.S.C. § 133). | . , . | |
| Status | | | | | |
| · — | Responsive to communication(s) filed on This action is FINAL . 2b) Since this application is in condition for a closed in accordance with the practice un | This action is non-final. allowance except for formal | • | he merits is | |
| Disposit | ion of Claims | | | | |
| 5)□ 6)⊠ 7)□ 8)□ Applicat i | Claim(s) 1-5,7-10 and 12-30 is/are pendid 4a) Of the above claim(s) 1-3 is/are with a claim(s) is/are allowed. Claim(s) 4,5,7-10 and 12-30 is/are reject claim(s) is/are objected to. Claim(s) are subject to restriction ion Papers The specification is objected to by the Example drawing(s) filed on is/are: a) Applicant may not request that any objection Replacement drawing sheet(s) including the content of the specific or sheet (s) includi | Irawn from consideration. ed. and/or election requirement aminer. □ accepted or b) □ objected to the drawing(s) be held in a | ed to by the Examiner. beyance. See 37 CFR 1.85(a). | | |
| 11) | The oath or declaration is objected to by | the Examiner. Note the atta | ached Office Action or form F | PTO-152. | |
| Priority ι | under 35 U.S.C. § 119 | | | | |
| a) | Acknowledgment is made of a claim for for All b) Some * c) None of: 1. Certified copies of the priority docu 2. Certified copies of the priority docu 3. Copies of the certified copies of the application from the International Elee the attached detailed Office action for | uments have been received uments have been received e priority documents have to Bureau (PCT Rule 17.2(a)). | I. I in Application No been received in this Nationa | al Stage | |
| Attachmen | • • | 🗖 . | | | |
| 2) 🔲 Notic 3) 🔲 Infori | ce of References Cited (PTO-892) ce of Draftsperson's Patent Drawing Review (PTO-9- mation Disclosure Statement(s) (PTO-1449 or PTO/ er No(s)/Mail Date | 48) Pape | view Summary (PTO-413) er No(s)/Mail Date ce of Informal Patent Application (P [*] er: | TO-152) | |

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DETAILED ACTION

Continued Examination Under 37 CFR 1.114

- 1. A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on 11/17/05 has been entered.
- 2. The Amendment filed 11/17/05 successfully overcomes the rejections set forth in paragraphs 3 and 4 of the Office Action mailed 8/19/05. Accordingly, these rejections are withdrawn.

Claim Rejections - 35 USC § 102

3. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 4, 5, 7-10 and 12-30 are rejected under 35 U.S.C. 102(b) as being anticipated by US 6,162,589 to Chen et al. (Chen). Chen discloses a method of manufacturing a thermal inkjet printhead comprising the steps of forming a layer of slow-crosslinking polymer, for example an epoxy or a polyimide, on a substrate;

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exposing the polymer layer through a single mask having multi-density levels to allow different dosages of electromagnetic energy to expose the polymer; developing to remove non cross-linked material to form a fluid-well chamber and an orifice chamber; and etching the through backside of the substrate to create a fluid feed channel. See column 8, lines 5-21 and Figures 9E-G.

Furthermore, as shown in Figure 9E, the multi-density level mask transmits electromagnetic radiation having regions of strong intensity 11 (corresponding to the first part having a relatively high UV transmission rate of the present invention), regions with a low dose of electromagnetic energy 12 (corresponding to the second and forth parts having the same relatively low UV transmission rate of the present invention), and provides a region where electromagnetic radiation is not transmitted at the orifice opening 42 (corresponding to the third part having a UV transmission rate of 0% of the present invention), wherein the region where electromagnetic radiation is not transmitted (i.e. the third part) is between the regions with a low dose of electromagnetic energy (i.e. the second and forth parts).

Response to Arguments

4. Applicant's arguments filed 11/17/05 have been fully considered but they are not persuasive. Applicant argues that the mask of Chen [as shown in figure 6A] has an opaque area **142** within a partially opaque area **144**. Thus, the opaque area **142** is not between different parts having a same UV transmission rate. However, Figure 6A of Chen is a top view of multi-density level mask **140**. If the mask of Chen was viewed as

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a cross section, similar to the view of photomask 108' in Figure 4C of the present invention, then the mask of Chen would comprise an opaque area between two partially opaque areas. This is clearly show in Figure 9E of Chen, where the length of the arrows, or lack thereof, represents the transmission rate of the mask. Note that the orifice opening 42, patterned by the opaque area 142 of multi-density level mask 140, is between two regions with a low dosage of electromagnetic energy 12, each patterned by partially opaque area 144 of multi-density level mask 140.

5. Any inquiry concerning this communication or earlier communications from the examiner should be directed to John A. McPherson whose telephone number is (571) 272-1386. The examiner can normally be reached on Monday through Friday, 8:00 AM to 4:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark Huff can be reached on (571) 272-1385. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should

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you have questions on access to the Private PAIR system, contact the Electronic

Business Center (EBC) at 866-217-9197 (toll-free).

John A. McPherson Primary Examiner Art Unit 1756

JAM 1/30/06